

VE 320 – Summer 2012 Introduction to Semiconductor Device

Non-ideal Effect, AC Response

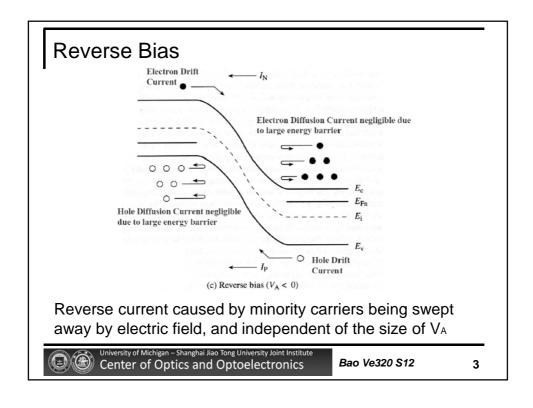
Instructor: Professor Hua Bao

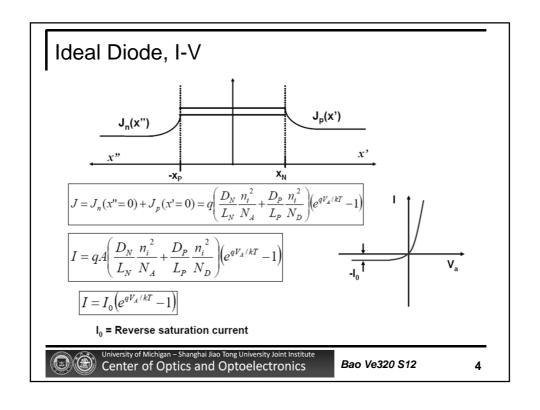
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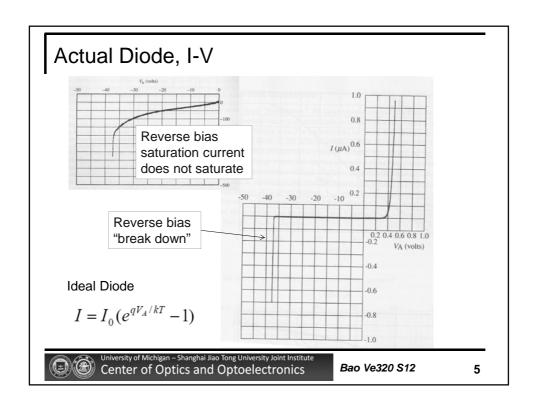
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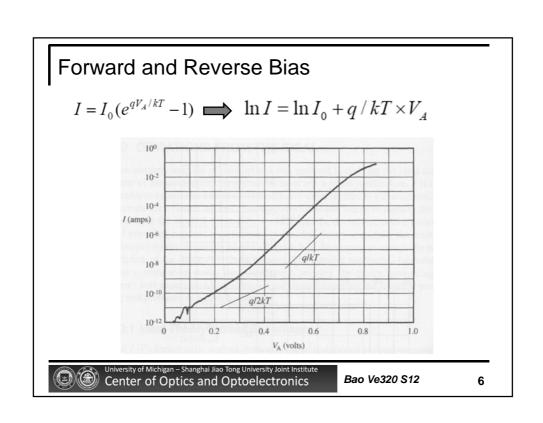
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Forward Bias Electron Diffusion Current Current Hole Diffusion Current Lectron Drift Current Fen Electron Diffusion Current Lectron Drift Current Lectron Drift Current Lectron Diffusion Current Electron Diffusion Current Lectron Drift Current Lectron Drift Current Lectron Drift Lectron Drift Current Lectron Drift Lectr





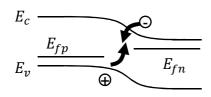


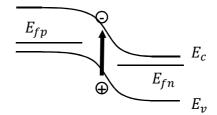


R-G In Depletion Region

Forward bias, injected carriers recombine in depletion region

Reverse bias, carriers generated in depletion region





How does the I-V relation of the diode change if R-G in depletion region is considered?



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R-G Current
$$I_{R-G}=qA\int\limits_{-x_p}^{x_n}\frac{\partial n}{\partial t}\bigg|_{R-G}dx$$
 General thermal R-G

$$\frac{\partial n}{\partial t}\bigg|_{R-G} = -\frac{np - n_i^2}{\tau_p(n+n_1) + \tau_n(p+p_1)} \qquad \begin{array}{ccc} n_1 & \equiv & n_i e^{(E_T-E_i)/kT} \\ p_1 & \equiv & n_i e^{(E_I-E_T)/kT} \end{array}$$

For reverse bias > a few kT/q

$$I_{R-G} \approx -\frac{qAn_i}{2\tau_0}W$$

For small (?) forward bias > a few kT/q

$$I_{R-G} \approx \frac{qAn_i}{2\tau_0} W e^{qV_A/2kT}$$

Full expression see RFP, Eq. (6.45)



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R-G In Depletion Region, Reverse Bias

Assume $E_T=E_i$ $au_n= au_p$

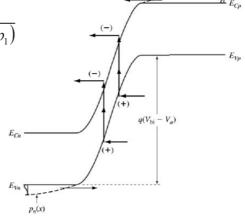
$$\left. \frac{\partial n}{\partial t} \right|_{R-G} = -\frac{np - n_i^2}{\tau_p(n+n_1) + \tau_n(p+p_1)}$$

$$R - G = \frac{np - n_i^2}{\tau_0 (n + n_i + p + n_i)}$$

At reverse bias (n, p negligible)

$$R - G = -\frac{n_i}{2\tau_0}$$

$$J_{GR} = q(R - G)w = -q\frac{n_i}{2\tau_0}w$$

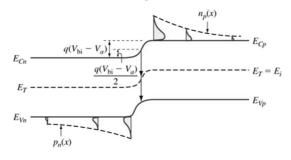


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R-G In Depletion Region, Forward Bias



$$R - G = \frac{np}{\tau_0(n+p)} = \frac{n_i^2 e^{qV_A/kT}}{\tau_0(n+p)}$$

$$J_{GR} = J_{GR0} \left(e^{qV_A/2kT} - 1 \right)$$

$$\left(R - G \right)_{\text{max}} = \frac{n_i e^{qV_A/2kT}}{2\tau_0}$$

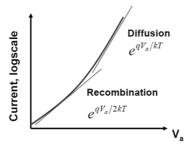
$$J = J_{GR0} \left(e^{qV_A/2kT} - 1 \right) + J_0 \left(e^{qV_A/kT} - 1 \right)$$

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Diffusion and R-G Current



- · Recombination dominant at low bias
- Diffusion dominates at larger bias
- Recombination often represented by nonideality factor (η) at given bias

 $\overline{J_{total}} = \overline{J_{diff}} + \overline{J_{GR}}$ For both forward and reverse bias cases

$$\begin{split} J_{total} &= J_0^{\textit{diff}} \Big(e^{qV_A/kT} - 1 \Big) + J_0^{\textit{GR}} \big(e^{qV_A/2kT} - 1 \big) \\ J_{total} &= J_0 \Big(e^{qV_A/\eta kT} - 1 \Big) \end{split}$$

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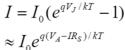
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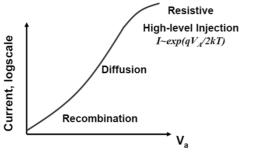
High Current Levels

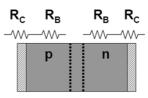
At high forward bias, I-V becomes resistive

$$V_J = V_A - IR_S$$

- Resistive drop across bulk semiconductor regions
- Contact resistance
- High-level injection: minority carrier density approaches majority carrier density

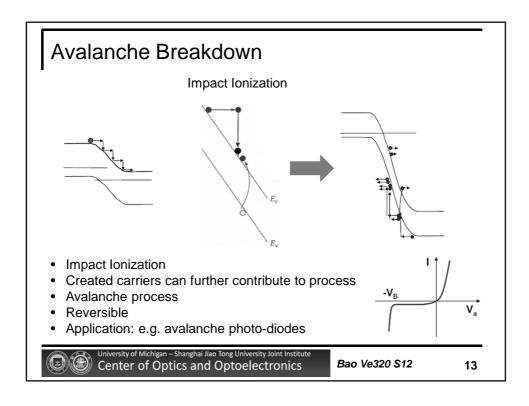


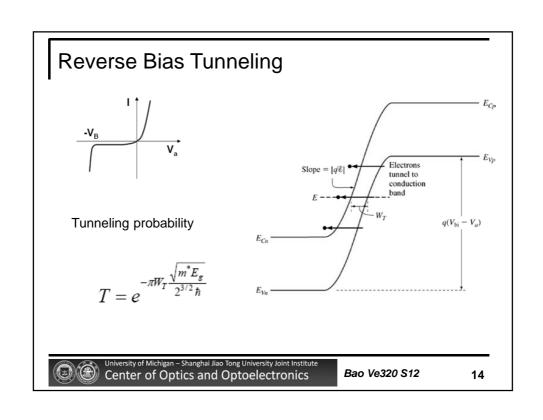




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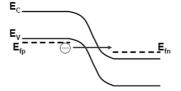
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Tunneling –Zener Breakdown

Narrow depletion region widths in reverse bias can enable quantum mechanical tunneling



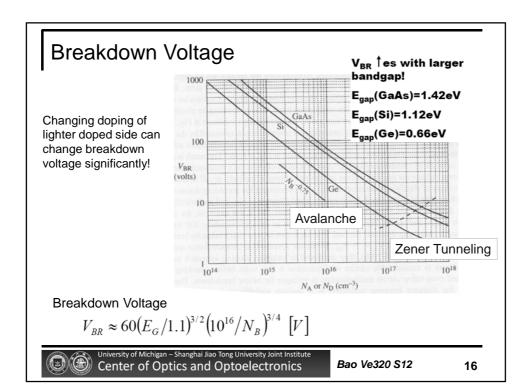
Tunneling Probability

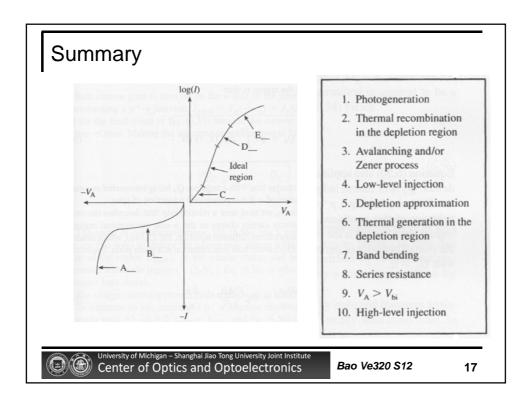
$$T \approx \exp\left(-\frac{4\sqrt{2m^*}}{3q\hbar\delta}E_G^{3/2}\right)$$

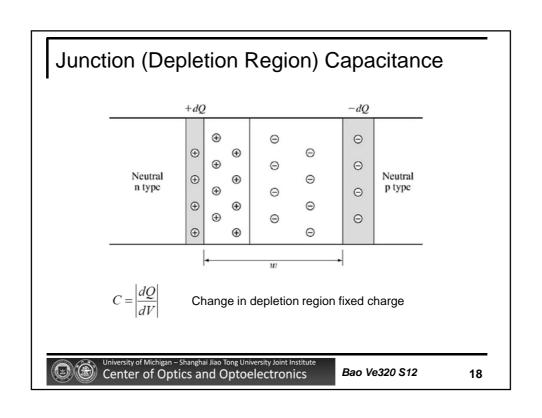
- "Barrier Thickness" is approximately equal to the depletion depth
- Important for samples with heavy doping (on both sides of the junction)



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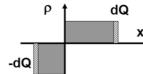




Junction Capacitance

Differential Capacitance

$$C = \left| \frac{dQ}{dV} \right|$$

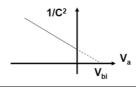


Capacitance associated with depletion region

$$\left|Q\right|=qN_{a}W_{_{D}}A=qN_{d}W_{_{n}}A$$

$$\boxed{C_j = A\sqrt{\frac{q \, \varepsilon N_a N_d}{2 \left(V_{bi} - V_a\right) \left(N_d + N_a\right)}} = \frac{\varepsilon A}{W}}$$

$$C_{j} = C_{j0} / \sqrt{1 - \frac{V_{a}}{V_{bi}}}$$



Depletion capacitance is proportional to applied voltage, Used as a voltagedependent capacitor (varactor)



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Diffusion Capacitance

Excess minority carrier density near depletion region edge is stored charge ->capacitance

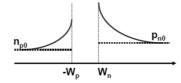
$$C = \left| \frac{dQ}{dV} \right|$$

$$\begin{split} Q_p &= qA\!\int_{x_n}^\infty\! \! \left[p_n(x)\!-p_{n0}\right]\!\!dx \\ Q_p &= qAp_{n0}L_p\!\left(\!e^{qV_a/kT}\!-\!1\right) \end{split}$$

$$Q_p = qAp_{n0}L_p \left(e^{qV_a/kT} - 1\right)$$

$$Q_p = J_{p_n}(x_n) A \tau_p = I_p \tau_p$$

$$C_D = \frac{q}{kT} \tau_p I_S e^{qV_a/kT}$$



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Junction and Diffusion Capacitance

How are junction and diffusion capacitance related?

$$\boxed{C_j = A\sqrt{\frac{q \, \varepsilon N_a N_d}{2 \big(V_{bi} - V_a \big) \big(N_d + N_a \big)}} = \frac{\varepsilon A}{W}}$$

$$C_D = \frac{q}{kT} \tau_p I_S e^{qV_a/kT}$$

Under what conditions are each dominant? Why?

Detailed discussion, including cases in which the (minority) carriers cannot follow up with the applied signal (non quasistatic cases), can be found in Pierret, Ch. 7.



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